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AMPLIFIED RESIST COMPOSITION, AND
PATTERNING PROCESS**(71) Applicant: **Shin-Etsu Chemical Co., Ltd.**, Tokyo
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(2013.01)(57) **ABSTRACT**

A novel salt having an amide bond in its anion structure is provided. A chemically amplified resist composition comprising the salt has advantages including minimal defects and improved values of sensitivity, LWR, MEF and CDU, when processed by lithography using high-energy radiation such as KrF excimer laser, ArF excimer laser, EB or EUV.